

FIG. 1

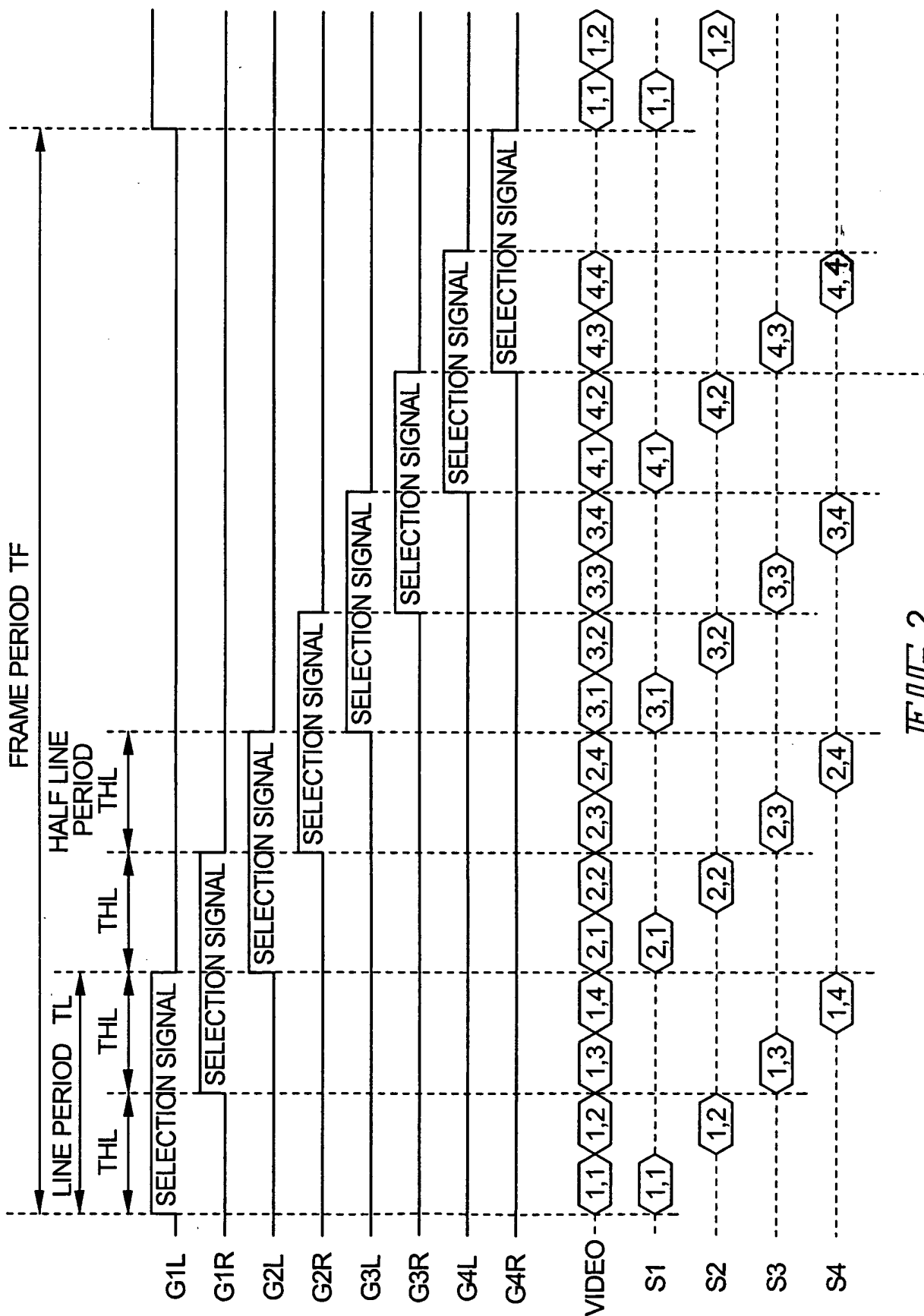


FIG. 2



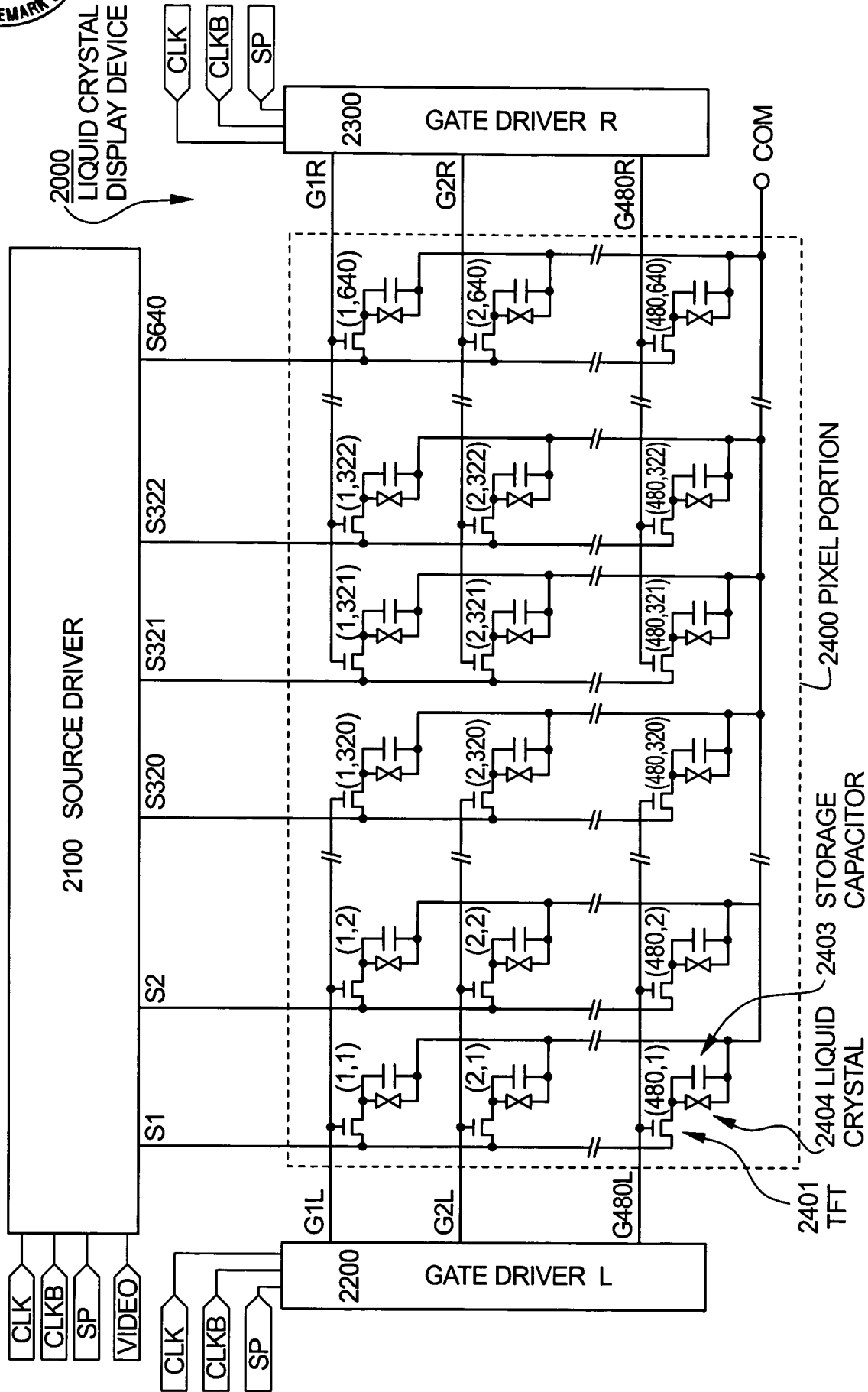


FIG. 3

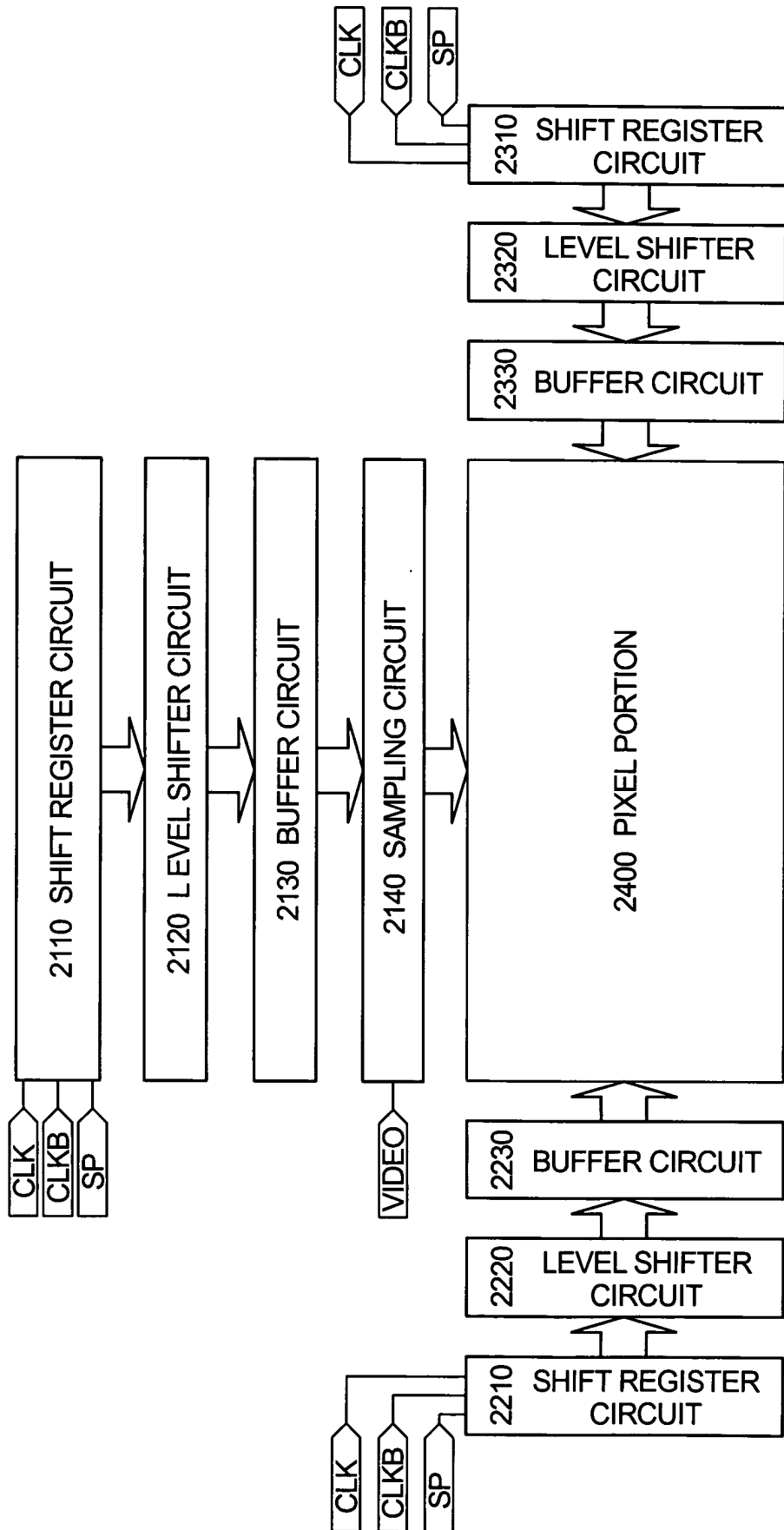


FIG. 4

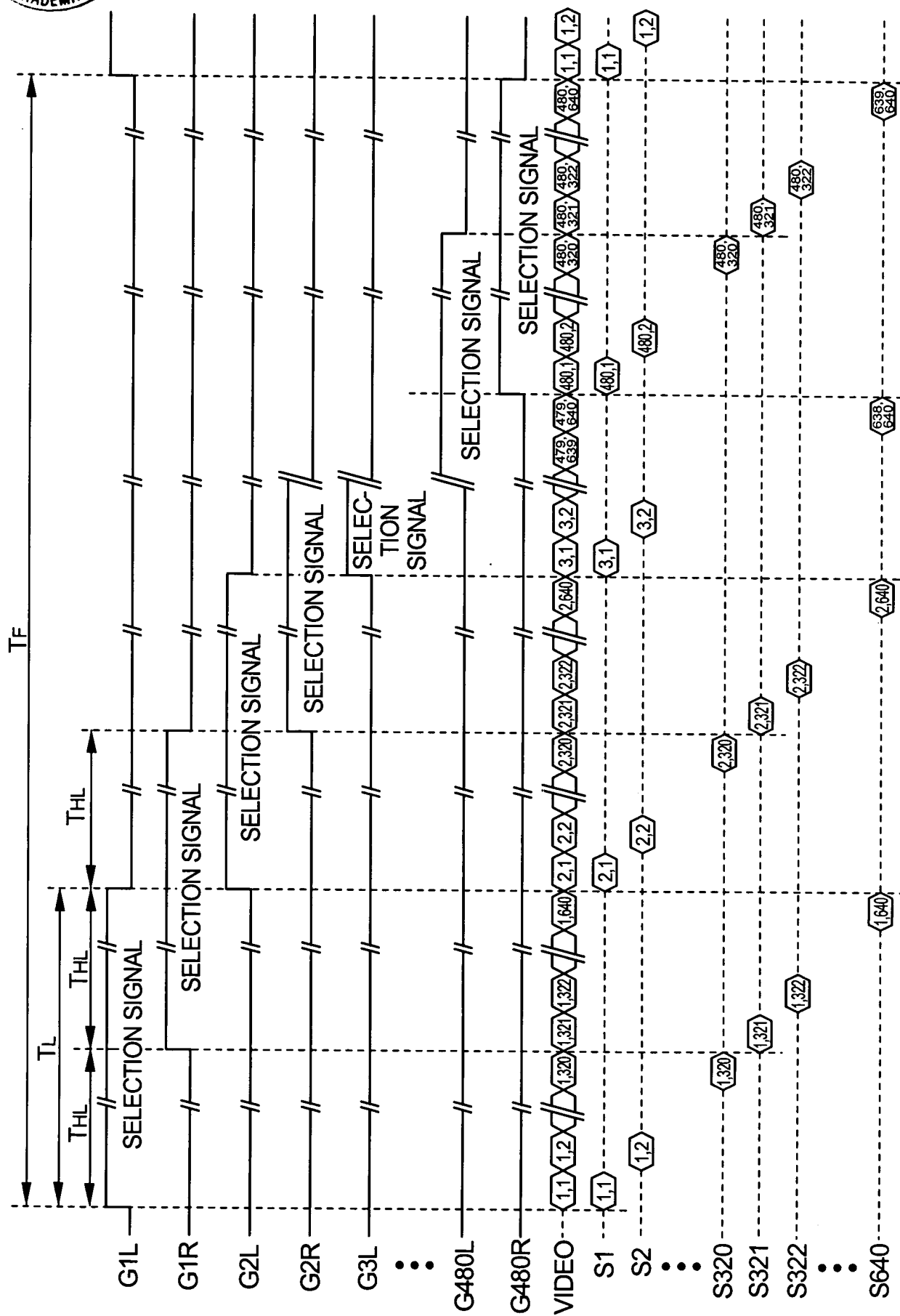


FIG. 5

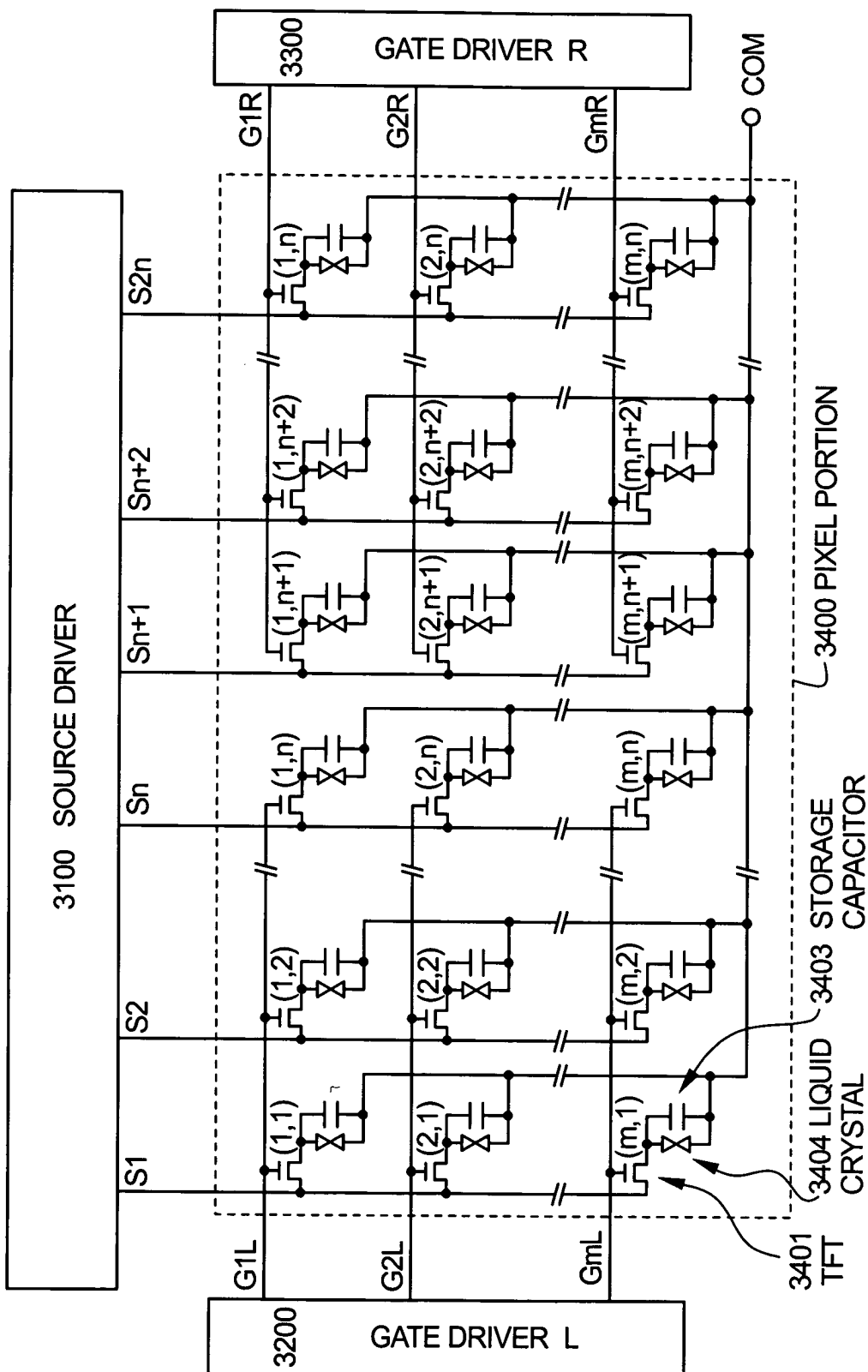


FIG. 6

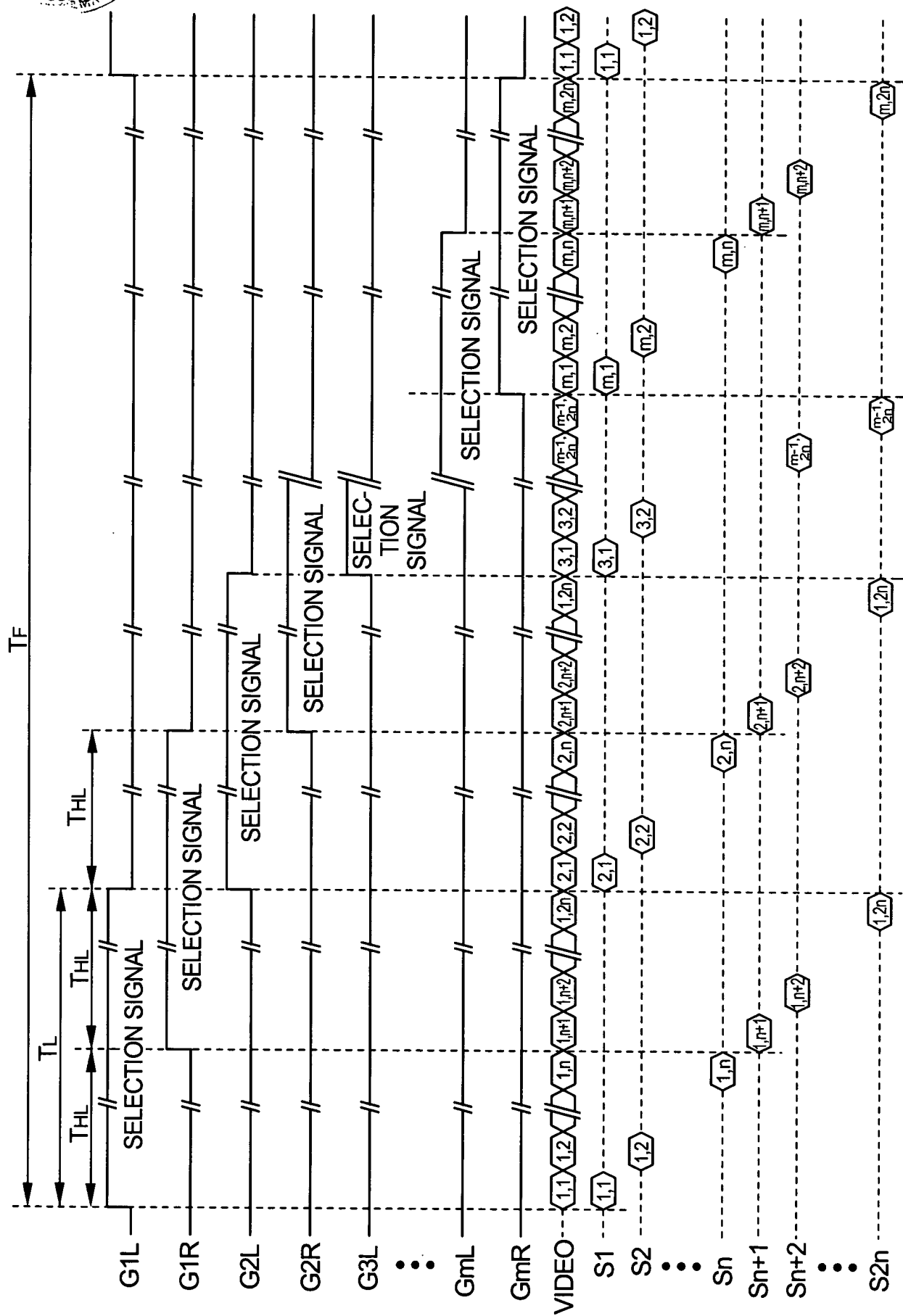


FIG. 7

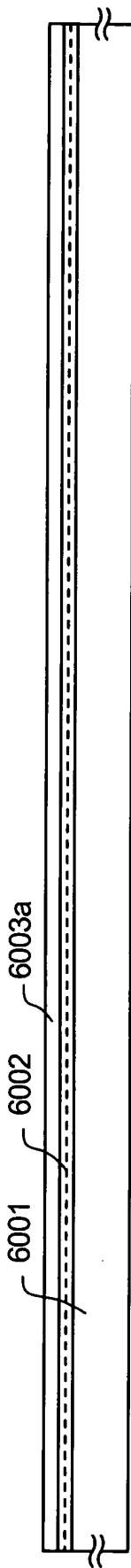


FIG. 8A

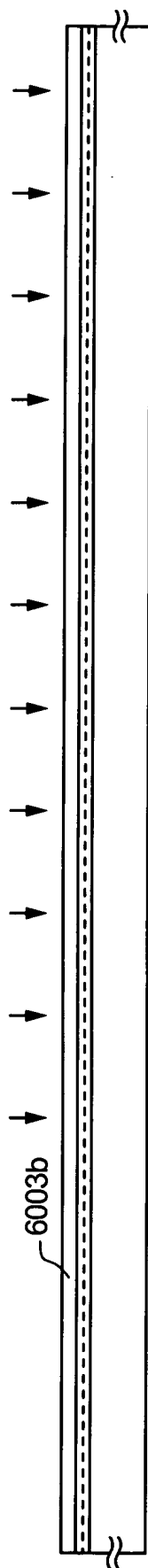


FIG. 8B

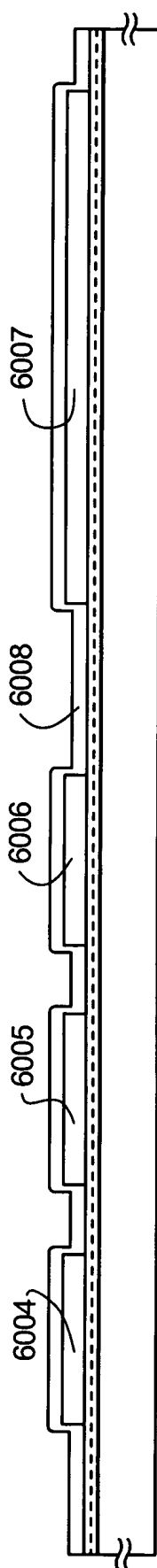


FIG. 8C

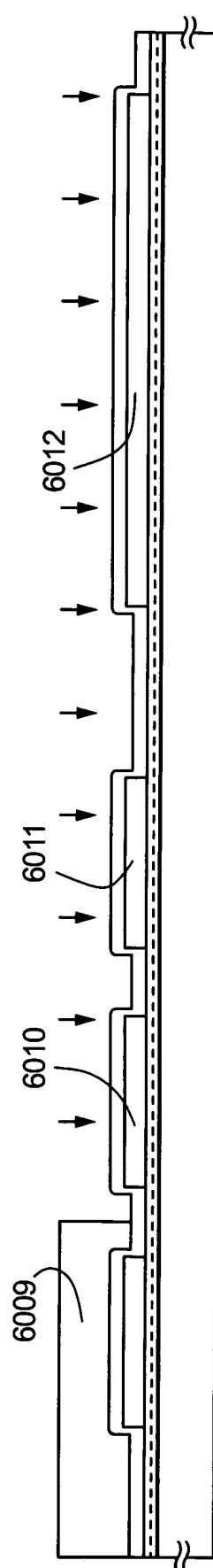


FIG. 8D

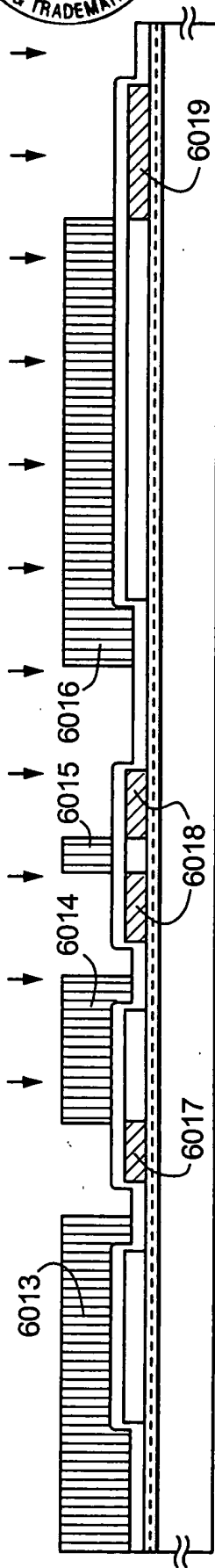


FIG. 9A

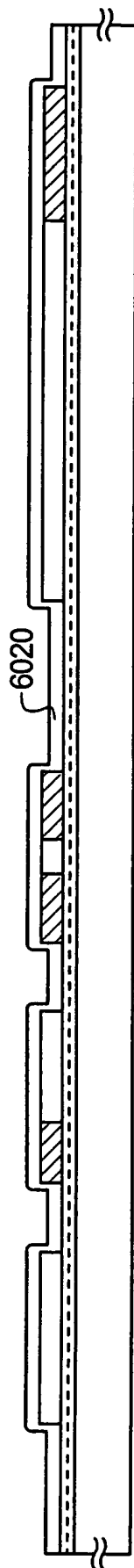


FIG. 9B

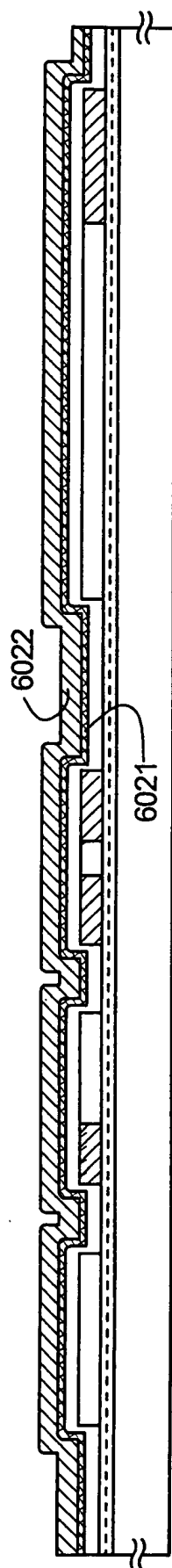


FIG. 9C

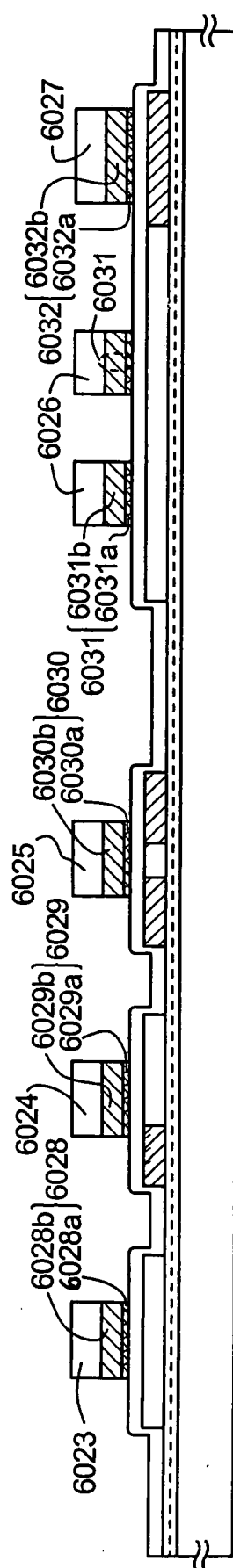


FIG. 9D

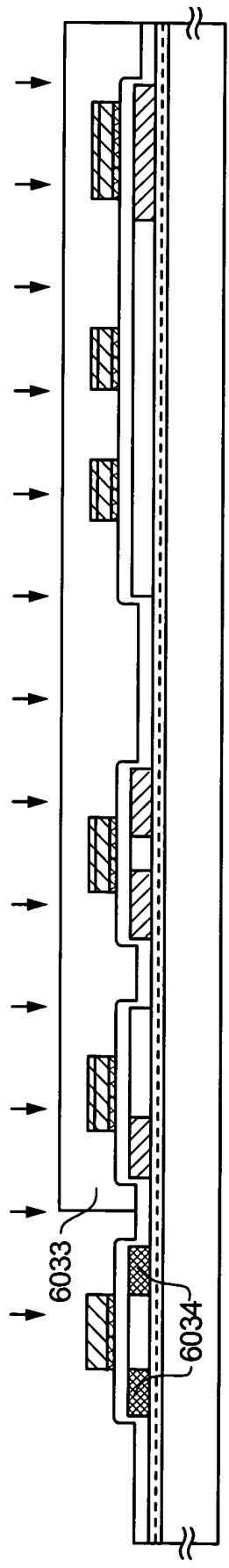


FIG. 10A

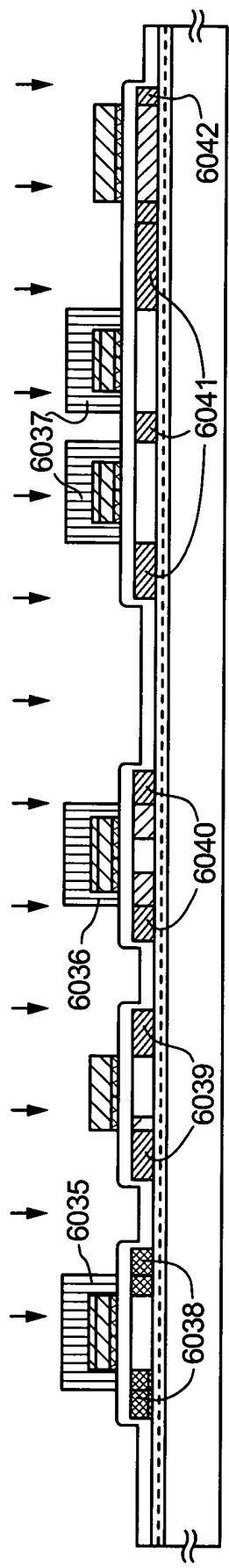


FIG. 10B

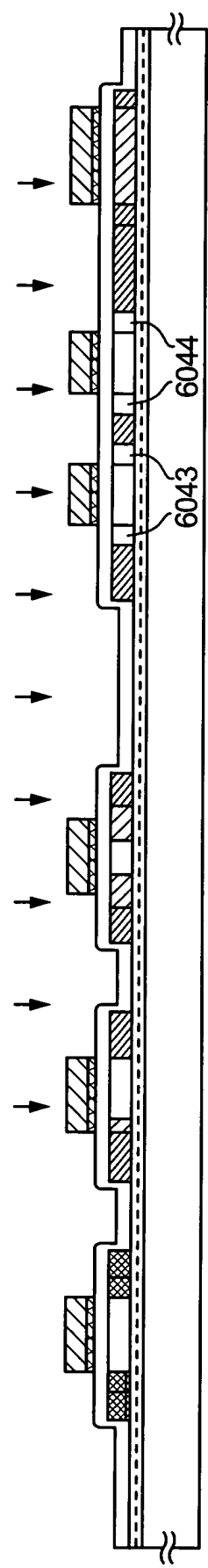


FIG. 10C

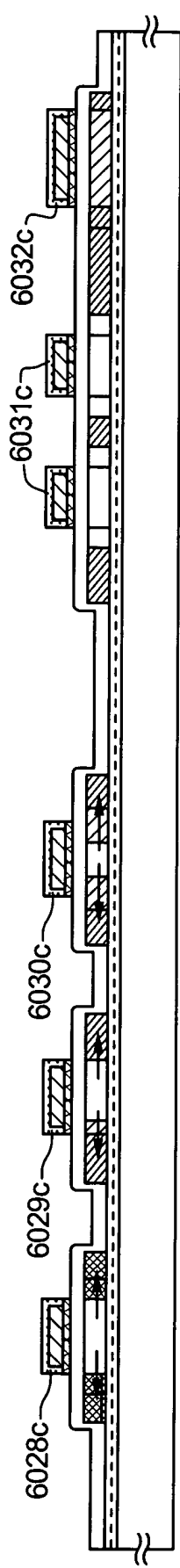


FIG. 10D

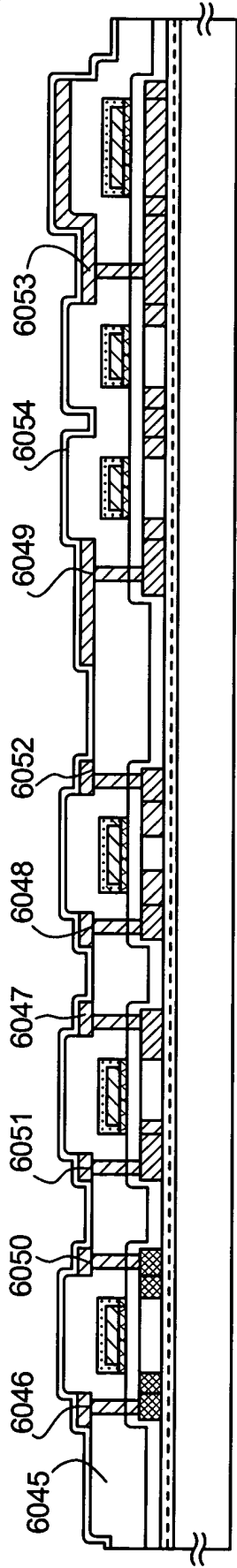


FIG. 11A

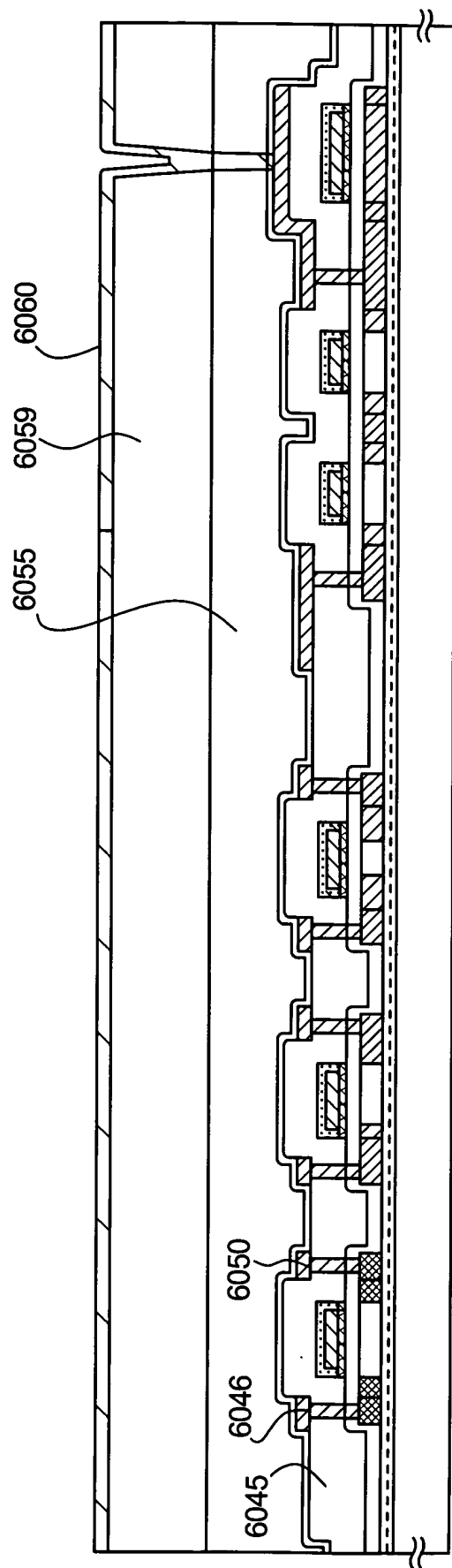
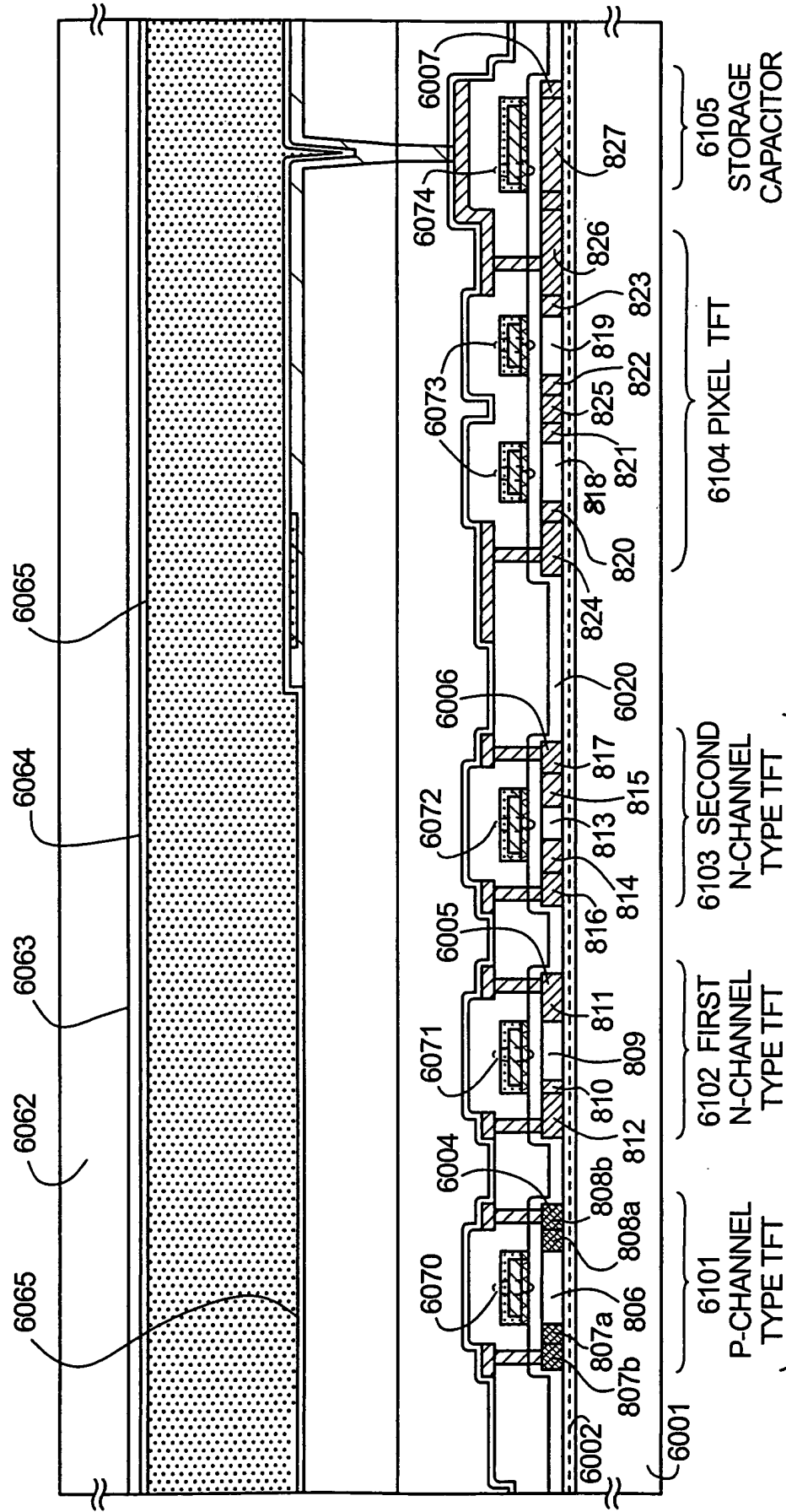
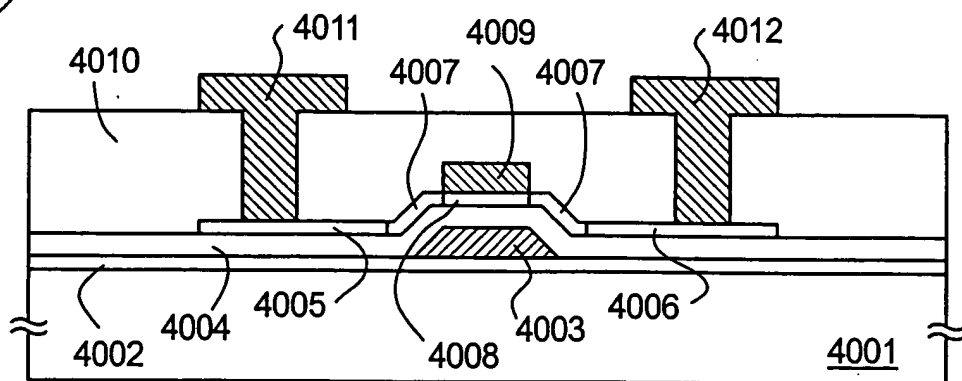
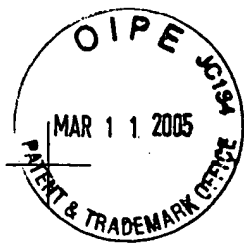


FIG. 11B

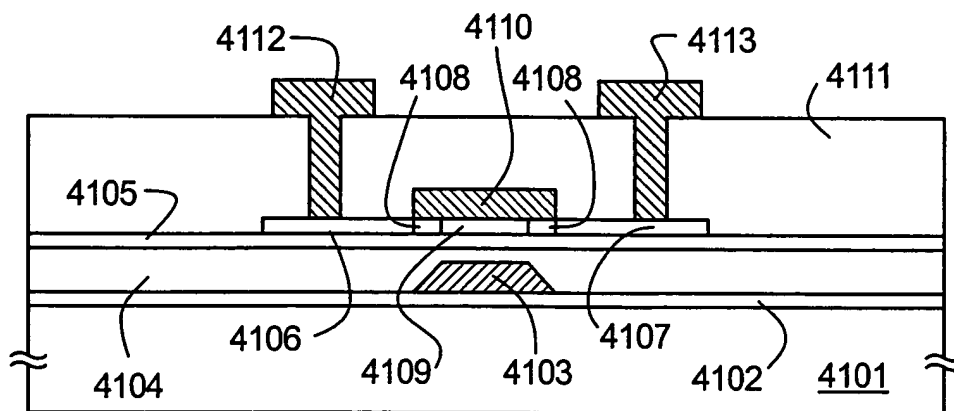


DRIVING CIRCUIT
 FIG. 12



- | | |
|---------------------------|--|
| 4001 SUBSTRATE | 4007 LOW CONCENTRATION IMPURITY REGION(LDD REGION) |
| 4002 SILICON OXIDE FILM | 4008 CHANNEL FORMING REGION |
| 4003 GATE ELECTRODE | 4009 CHANNEL PROTECTING FILM |
| 4004 GATE INSULATING FILM | 4010 INTERLAYER INSULATING FILM |
| 4005 SOURCE REGION | 4011 SOURCE ELECTRODE |
| 4006 DRAIN REGION | 4012 DRAIN ELECTRODE |

FIG. 13A



- | | |
|----------------------------|--|
| 4101 SUBSTRATE | 4108 LOW CONCENTRATION IMPURITY REGION(LDD REGION) |
| 4102 SILICON OXIDE FILM | 4109 CHANNEL FORMING REGION |
| 4103 GATE ELECTRODE | 4110 CHANNEL PROTECTING FILM |
| 4104 BENZOCYCLOBUTENE(BCB) | 4111 INTERLAYER INSULATING FILM |
| 4105 SILICON NITRIDE FILM | 4112 SOURCE ELECTRODE |
| 4106 SOURCE REGION | 4113 DRAIN ELECTRODE |
| 4107 DRAIN REGION | |

FIG. 13B



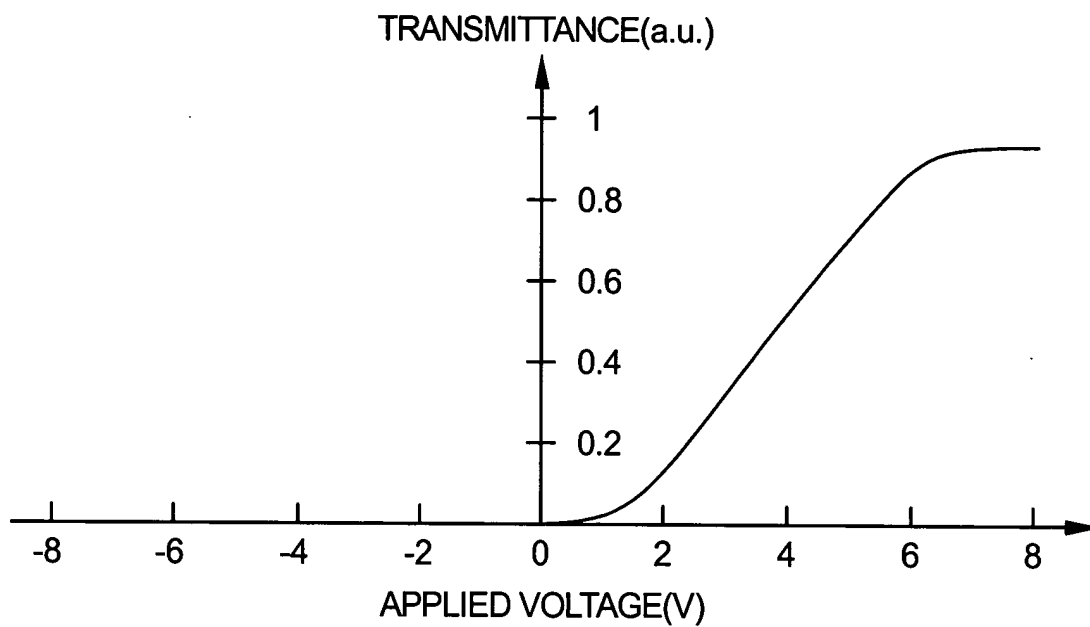
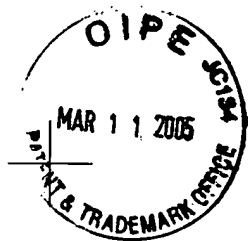


FIG. 14



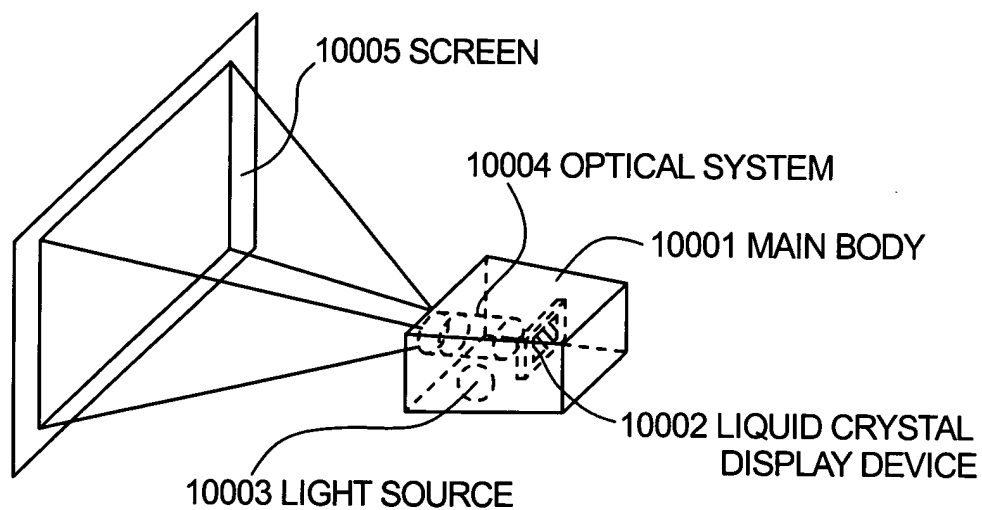


FIG. 15A

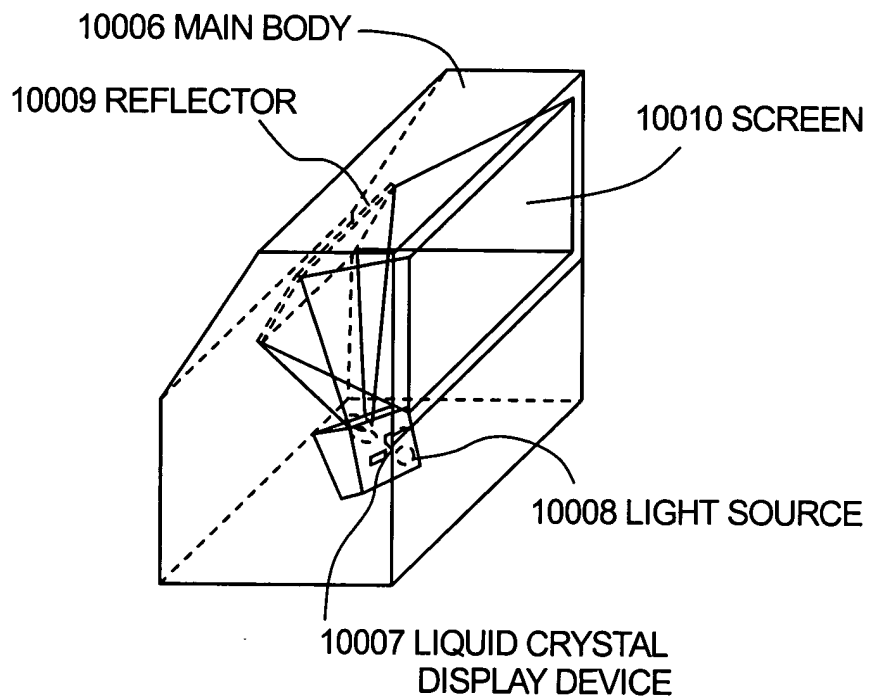


FIG. 15B

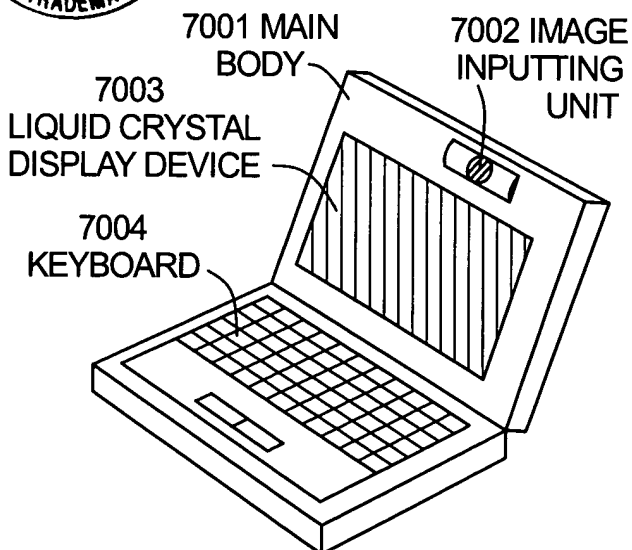
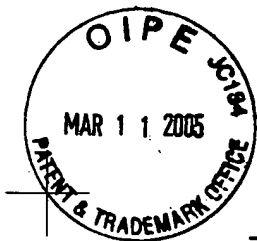


FIG. 16A

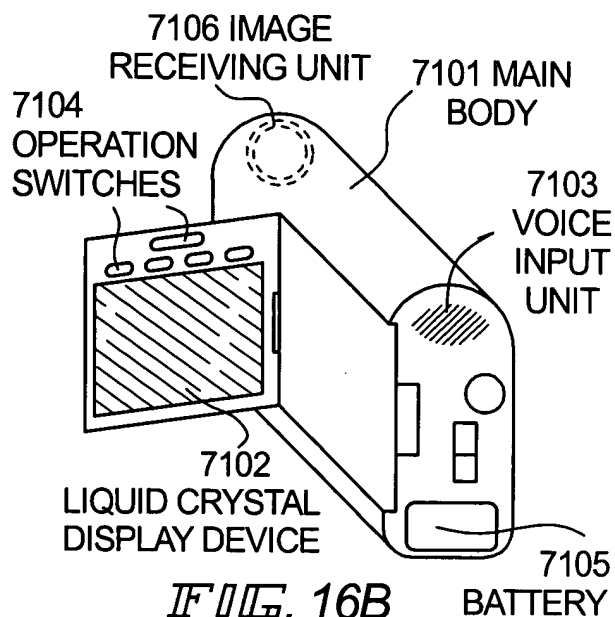


FIG. 16B

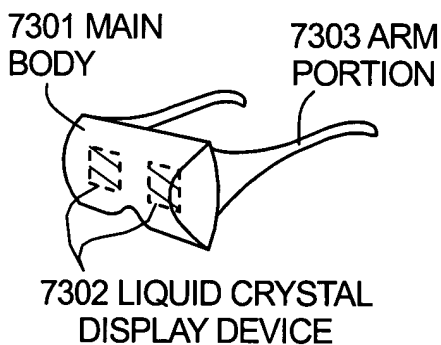


FIG. 16D

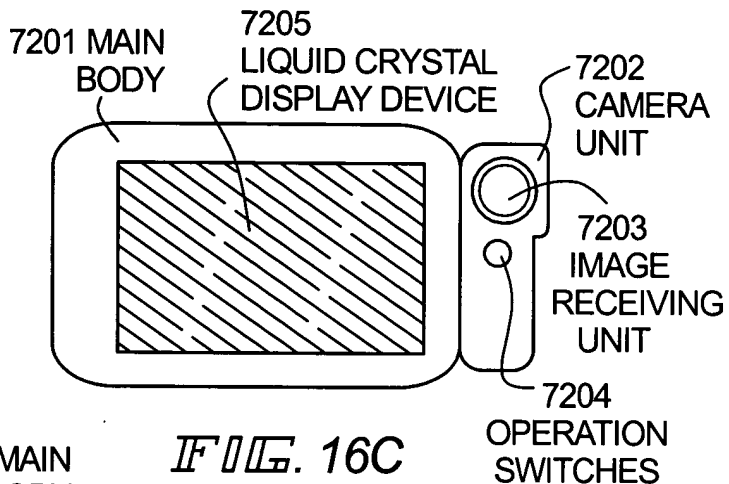


FIG. 16C

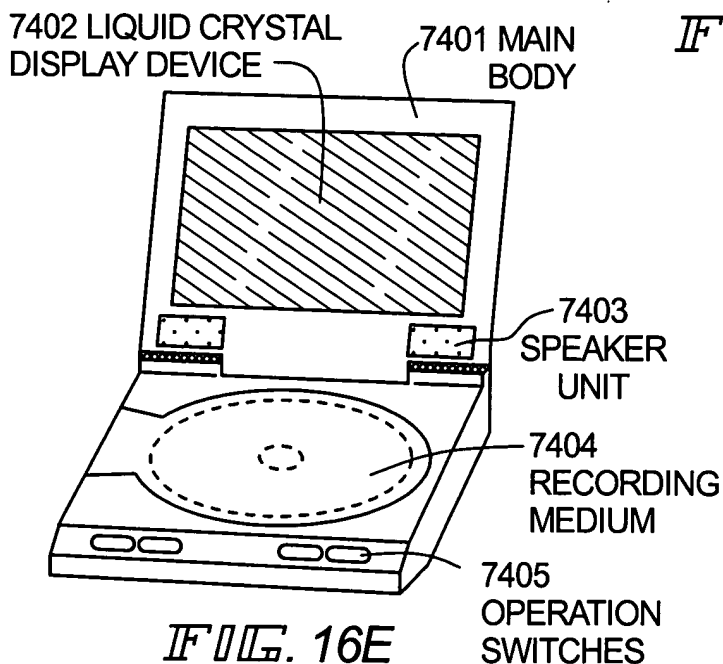


FIG. 16E

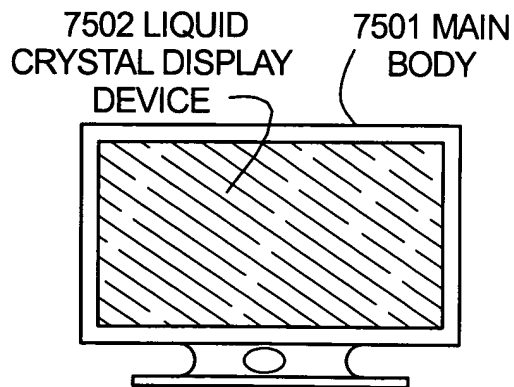


FIG. 16F

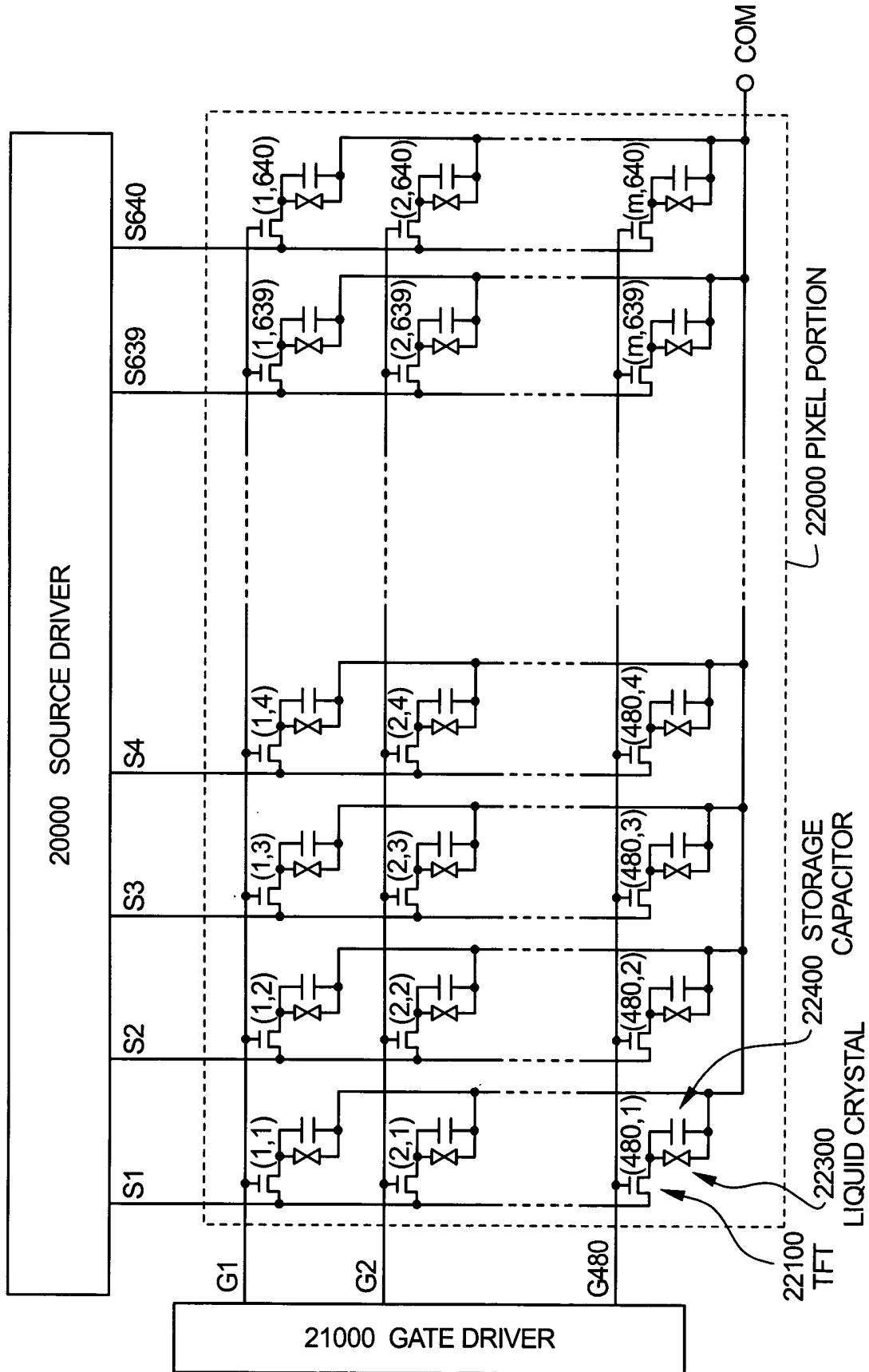
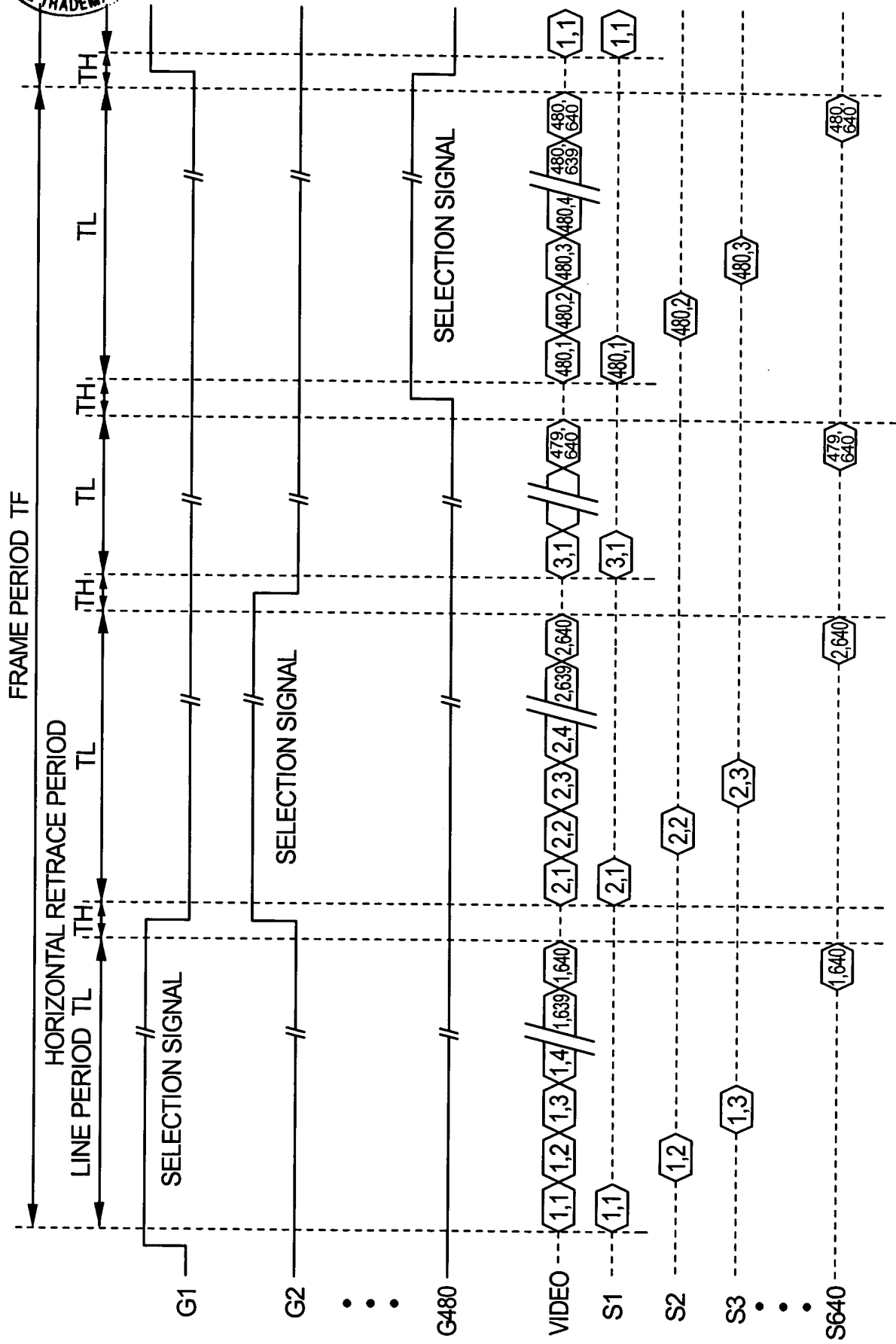


FIG. 17



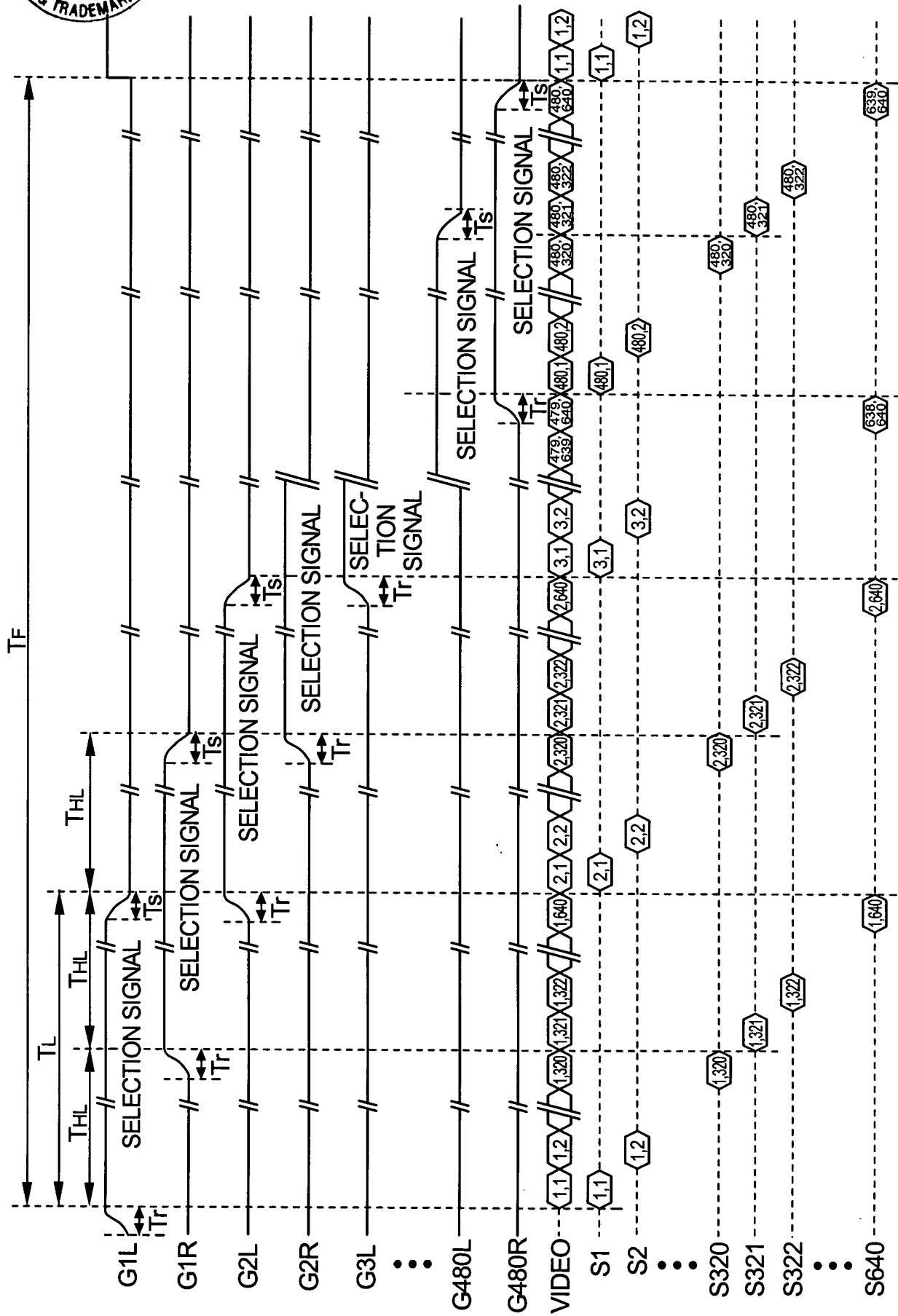


FIG. 19

